

Technical Program

Time	2 July (Day 0) - Tutorials			
	Symposium Room II		Symposium Room I	
	Session TUT A: Tutorials (Reliability) Session Chair: Wardhana A. Sasangka <i>Singapore-MIT Alliance for Research and Technology, Singapore</i>		Session TUT B: Tutorials (Failure Analysis) Session Chair: Sun Litao <i>Southeast University, China</i>	
08:30-10:30	TUT A1	Reliability of 3D Through-Silicon Via (TSV) Technologies Dr. Dimitris P. Ioannou <i>Globalfoundries, USA</i>	TUT B1	Principles and Applications of TEM and FIB in the Semiconductor Industry Dr. David Su <i>TSMC, Taiwan (Retired)</i>
10:30-10:45	Tea Break			
10:45-12:45	TUT A2	BTI: Testing and Predictive Modeling Prof. Jianfu Zhang <i>Liverpool John Moores University, UK</i>	TUT B2	Advanced 2.5D/3D Package Level Failure Analysis Dr. Lihong Cao <i>ASE Group, TX, USA</i>
12:45-13:45	Lunch			
13:45-15:45	TUT A3	Testing for Reliability of Power Electronic Components Prof. Francesco Iannuzzo <i>Aalborg University, Denmark</i>	TUT B3	Advanced Fault Isolation Technologies: Design House and Foundry Perspectives: PART I Mr. Venkat Krishnan Ravikumar <i>AMD, Singapore</i>
15:45-16:00	Tea Break			
16:00-18:00	TUT A4	MOL & BEOL Reliability Challenges for Advanced Technology Nodes Dr. Baozhen Li <i>IBM System and Technology Group, Essex Vermont, USA</i>	TUT B4	Advanced Fault Isolation Technologies: Design House and Foundry Perspectives: PART II Dr. Szu Huat Goh <i>GlobalFoundries, Singapore</i>
End of Day 0				

Time	3 July (Day 1)			
09:00-09:10	Opening Address by General Chair - Prof. Juin J. Liou <i>Zhengzhou University, China</i>			
09:10-09:15	Technical Program Briefing by TPC Chair - Zhiwei Liu <i>UESTC, China</i>			
09:15-09:20	IPFA 2018 Best Papers Award Presentation			
09:20-10:20	KN.1 Session Chair: Juin J. Liou	Building Reliable Products Guided by Customer Obsession Prasad Chaparala <i>Amazon Lab126, USA</i>		
10:20-10:40	Tea Break			
	Symposium Room II		Symposium Room I	
	Session 1A: Logic / NVM Device Reliability Session Chair: Jiezhi Chen <i>Shandong University, China</i>		Session 1B: Package Level Failure Analysis Session Chair: Hong Yang <i>IME, CAS, China</i>	
10:40-11:10	Paper ID: 331 Invited (1A.1)	Challenge and solution for characterizing NBTI-generated defects in nanoscale devices Jianfu Zhang <i>Liverpool John Moores University, UK</i>	Invited (1B.1)	Challenge for Advanced Package Level Fault Isolation Lihong Cao <i>ASE Group, Austin, TX, USA</i>
11:10-11:30	Paper ID: 289 (1A.2)	Experiment Characterization of Front and Back Interfaces Impact on Back Gate Modulation in UTBB-FDSOI MOSFETs Wangyong Chen et al. <i>Institute of Microelectronics, Peking University, China</i>	Paper ID: 261 (1B.2)	Improvement of sensitivity of ultrasonic beam induced resistance change (SOBIRCH) method with ultrasound resonance in the mold resin Takuto Matsui et al. <i>Toyohashi University of Technology, Japan</i>
11:30-11:50	Paper ID: 301 (1A.3)	Resistive switching in atomic layer deposited and sputtered TiO2 films: electroforming observed by constant voltage stress Tao Wang et al. <i>Soochow University, China</i>	Paper ID: 298 (1B.3)	Enhancement of localization capability of lock-in thermography for power semiconductor devices by searching high-emissivity films Norimichi Chinone, Toru Matsumoto and Kazushige Koshikawa <i>Hamamatsu Photonics K. K, Japan</i>
11:50-12:10	Paper ID: 283 (1A.4)	Output Breakdown Characteristics and the Related Degradation Behaviors in Metal Oxide Thin Film Transistors Xiaotong Ma et al. <i>Shenzhen University, China</i>	Paper ID: 128 (1B.4)	The probe marker discoloration on Al pad and wafer storage Wen-Fei Hsieh, Henry Lin, Vincent Chen, Irene Ou and YS Lou <i>Ardentec Cooperation, Taiwan, ROC</i>

<p>^12:10-12:40 *12:10-12:30</p>	<p>^Paper ID: 330 Invited (1A.5)</p>	<p>Advanced FinFET Device Reliability Mu-Chun Wang <i>MUST, Taiwan</i></p>	<p>*Paper ID: 226 (1B.5)</p>	<p>Signal Processing Method for Scanning Acoustic Tomography Defect Detection based on a Correlation between Ultrasound Waveforms Masayuki Kobayashi, Kaoru Sakai, Kenta Sumikawa and Osamu Kikuchi <i>Hitachi, Japan</i></p>
Lunch				
<p>Session 2A: Interconnect and Packaging Reliability Session Chair: Wardhana A. Sasangka <i>Singapore-MIT Alliance for Research and Technology, Singapore</i></p>		<p>Session 2B: Case Studies on Fault Isolation Session Chair: Christian Boit <i>TU Berlin, Germany</i></p>		
<p>13:40-14:10</p>	<p>Paper ID: 337 Invited (2A.1)</p>	<p>Advanced On-Chip Interconnect Reliability Baozhen Li <i>IBM System and Technology Group, Essex Vermont, USA</i></p>	<p>Invited (2B.1)</p>	<p>Challenges in laser probing at spatial resolution compromised technology nodes Venkat Krishnan Ravikumar <i>AMD Singapore</i></p>
<p>14:10-14:30</p>	<p>Paper ID: 162 (2A.2)</p>	<p>Self-heating aware EM Reliability Prediction of Advanced CMOS Technology by Kinetic Monte Carlo Method Linlin Cai et al. <i>Peking University, China</i></p>	<p>Paper ID: 200 (2B.2)</p>	<p>Using Microprobe to enhance Die Level Static Fault Isolation in Complex IC Dayanand Nagalingam et al. <i>Globalfoundries, Singapore</i></p>
<p>14:30-14:50</p>	<p>Paper ID: 275 (2A.3)</p>	<p>CPB fcCSP BGA Package Reliability assessment via the study of Bump Cross Section Morphology after Product Reliability stress testing Haitham Hamed and Vicky Wang <i>SK Hynix Memory Solutions, USA</i></p>	<p>Paper ID: 114 (2B.3)</p>	<p>Integrating NI LabVIEW in Soft Defect Localization of Temperature Dependent Voltage Failure Paul Hubert Llamera, Camille Joyce Garcia-Awitan, Febus Reidj Cruz and Glenn Magwili <i>Maxim Integrated, Philippines</i></p>
<p>14:50-15:10</p>	<p>Paper ID: 156 (2A.4)</p>	<p>Comparison of Cl effects on Au-Al and Cu-Al HTS and bHAST reliability Lois Jinzhi Liao et al. <i>Huawei Technologies, China</i></p>	<p>Paper ID: 185 (2B.4)</p>	<p>Increase Fault Isolation Efficiency by Using Scan Cell Visualizer for Scan Chain Failure Thin Wei Chua, Loke Sheng Foo, Kim Choo Ng and Keith Serrels <i>NXP Semiconductors, Malaysia</i></p>
Tea Break				

	Session 3: Exhibitor Session
15:30-18:00	<p> Thermo Fisher Scientific (8min) ZEISS (6min) INTEGRATED SERVICE TECHNOLOGY (6min) SEMICAPS PTE LTD (8min) Kleindiek Nanotechnik (4min) TELTEC SEMICONDUCTOR PACIFIC LTD (4min) Hamamatsu Photonics (China) Co.,Ltd. (4min) Shanghai Winner International Trading CO., Ltd (4min) Crest Systems (Suzhou) CO., Ltd (4min) Nordson Advanced Technology Systems (4min) IMINA TECHNOLOGIES (4min) Materials Analysis Technology (Shanghai) Ltd (4min) Hitachi High-Technologies Corporation (4min) Ellipsiz iNETEST Co., Ltd (4min) Ellipsiz iNETest Shanghai CO.,LTD -- SELA Ltd (4min) Ellipsiz iNETest Shanghai CO.,LTD -- DIGIT- CONCEPT (4min) DIGIT CONCEPT SAS (4min) HMC Sales & Service Pte Ltd (4min) GALLANT PRECISION MACHINING CO., LTD (4min) ZURICH INSTRUMENTS (4min) Semishare (shenzhen) technology CO., LTD (4min) ESDEMC Technology LLC (4min) Platform Design Automation, Inc. (4min) WinTech Nano (4min) Oxford Instruments (4min) Hitachi Power Solution Co. ,Ltd. (4min) AMETEK TMC (4min) Advantest Corporation (4min) Gold Medal Analytical & Testing Group (4min) Sanying Precision Instruments Co.,Ltd (4min) ATOM SEMICON COMPANY LTD. (4min) GIGA FORCE ELECTRONICS CO.,LTD, (4min) Toyo Corporation China (4min) HANWA ELECTRONIC IND.CO., LTD (4min) Radiant Optronics Pte. Ltd (4min) JIACO INSTRUMENTS (4min) Phenom Desktop SEM (4min) Hongzhunda Tech (4min) </p>
End of Day 1	

Time	4 July (Day 2)			
08:30-09:30	KN.2 Session Chair: Juin J. Liou	Emerging Non-Volatile Memory's Applications in Neuro-Inspired Computing and Hardware Security Shimeng Yu <i>Georgia Institute of Technology, USA</i>		
Session 4: Best Paper Exchange Session Chair : Nagarajan Raghavan, <i>SUTD, Singapore</i>				
09:30-10:00	ISTFA 2018 Exchange Paper (4.1)	Scan Chain Fault Isolation using Single Event Upsets Induced by a Picosecond 1064 nm Laser Keith Serrels <i>NXP Semiconductors, USA</i>		
10:00-10:30	ESREF 2018 Exchange Paper (4.2)	Further Improvements of an Extended Hakki-Paoli Method Massimo Vanzi <i>University of Cagliari, Italy</i>		
10:30-10:50	Tea Break			
	Symposium Room II		Symposium Room I	
	Session 5A: Transistor Reliability (ESD) Session Chair: Zhiwei Liu, <i>UESTC, China</i> and You Li, <i>Globalfoundries, USA</i>		Session 5B: Advanced Electrical Fault Isolation Techniques Session Chair: Venkat Krishnan Ravikumar <i>AMD, Singapore</i>	
10:50-11:20	Invited (5A.1)	ESD / advanced FinFET device reliability You Li <i>Globalfoundries, USA</i>	Invited (5B.1)	Quantitative MIS Characterization Through Electro-Optical Signals Christian Boit <i>TU Berlin, Germany</i>
11:20-11:40	Paper ID: 251 (5A.2)	Modeling and Simulation of Diode Triggered Silicon Controlled Rectifier Behavior Under ESD Stresses Meng Miao, You Li and Robert Gauthier <i>Globalfoundries, USA</i>	Paper ID: 308 (5B.2)	EOFM measurements of lateral and vertical Bipolar Transistors in Silicon and SiGe:C Technologies Anne Beyreuther, Tomonori Nakamura, Stefan Keil and Christian Boit <i>TU Berlin, Germany</i>
11:40-12:00	Paper ID: 203 (5A.3)	Investigation of Electrical Parameters Degradations for 600V SOI-LIGBT under Repetitive ESD Stresses Li Lu, Ran Ye, Siyang Liu and Weifeng Sun <i>Southeast University, China</i>	Paper ID: 307 (5B.3)	EOFM for contactless parameter extraction of low k dielectric MIS structures Norbert Herfurth, Stefan Keil, Tomonori Nakamura and Christian Boit <i>TU Berlin, Germany</i>
12:00-14:00	Lunch Poster Session			

14:00-14:20	Paper ID: 237 (5A.4)	A Systematic Failure Analysis Approach to Determine True Electrical Overstress Failures on Integrated Circuits Em Julius Dela Cruz <i>Maxim Integrated, Philippines</i>	Paper ID: 326 (5B.4)	Fault Localization Using Dynamic Optical-beam Induced Current Variation Mapping Man Hon Thor et al. <i>Globalfoundries, Singapore</i>
14:20-14:40	Paper ID: 150 (5A.5)	New Approaches in ESD Risk Measurement of PCB Assembling Machines and ESD Countermeasures Peter Jacob <i>Empa Duebendorf, Switzerland</i>	Paper ID: 325 (5B.5)	Accurate Memory Bitmapping based on Built-in Self-Test: Challenges and Solutions Lin Zhao, YT Ngow, SH Goh, YH Chan, Hao Hu <i>GLOBALFOUNDRIES, Product Diagnostic Engineering, Singapore</i> F Jeff, CC Tay <i>Mentor - A Siemens Business</i>
14:40-15:00	Paper ID: 285 (5A.6)	Failure Analysis of Microwave Module by ESD Effect Zhimin Ding et al. <i>China Academy of Space Technology, China</i>	Paper ID: 256 (5B.6)	Characterization of 1122nm Laser for Laser Based Fault Isolation Applications Vasanth Somasundaram, Yi Xuan Seah, Venkat Krishnan Ravikumar, Angeline Phoa and Choon Meng Chua <i>AMD, Singapore</i>
15:00-15:20	Paper ID: 204 (5A.7)	Capacitor Modeling Methodology for System-level ESD Simulation Li Xiang, Xie Xiaofei, Xia Nan and Gu Zhengdong <i>Huawei Technologies, China</i>	Paper ID: 121 (5B.7)	Cycle-Shift Scan Chain Failure Analysis Using Single Pulse Test Pattern Eric Paulraj, Chwee-Lin Choong and Yiang Won Chai <i>Intel Technologies, Malaysia</i>
15:20-15:40	Tea Break			
	Session 6A: Transistor Reliability Session Chair: Xinnan Lin <i>Peking University Shenzhen Graduate School</i>		Session 6B: Case Studies on Fault Isolation Session Chair: Szu Huat Goh <i>Globalfoundries, Singapore</i>	
15:40-16:10	Invited (6A.1)	Reliability of STTRAM Devices You Wang <i>Beihang University, China</i>	Paper ID: 334 Invited (6B.1)	Failure Analysis for Advanced Package Technology Ching-Chun Lin and Kim Hsu <i>Integrated Service Technology, Taiwan</i>
16:10-16:30	Paper ID: 210 (6A.2)	Understanding lifetime prediction methodology for In_{0.53}Ga_{0.47}As nFETs under Positive Bias Temperature Instability (PBTI) condition Zhigang Ji, Xiong Zhang and Jianfu Zhang	Paper ID: 191 (6B.2)	Root cause analysis on analog circuit using TR-LADA Winson Lua, Venkat Krishnan Ravikumar, Angeline Phoa, Gopinath Ranganathan and Girish AS <i>AMD, Singapore</i>

		<i>Liverpool John Moores University, China</i>		
16:30-16:50	Paper ID: 262 (6A.3)	Comparison of NBTI kinetics in RMG Si p-FinFETs featuring ALD W Filling Metal Using B₂H₆ and SiH₄ Precursors Longda Zhou et al. <i>University of Chinese Academy of Sciences, China</i>	Paper ID: 178 (6B.3)	Optical Failure Analysis on Pulsed Signals Embedded in Logic Cloud – A Case Study of Laser Voltage Tracing Yuzhu Sun et al. <i>Thermo Fisher Scientific, USA</i>
16:50-17:10	Paper ID: 279 (6A.4)	Impact of Channel Doping on NBTI Reliability and Variability in Nanoscale FinFETs Zhe Zhang, Runsheng Wang, Yangyuan Wang and Ru Huang <i>Peking University, China</i>	Paper ID: 305 (6B.4)	Methodology to Investigate the Root Cause of Threshold Voltage Drift of Transistor Devices using Capacitance Voltage Measurements Chung Keow Ang et al. <i>Infineon Technologies, Malaysia</i>
17:10-17:30	Paper ID: 264 (6A.5)	Study of Internal Latchup Behaviors in Advanced Bulk FinFET Technology Wei Liang, Robert Gaunthier Jr, Souvick Mitra, You Li <i>Globalfoundries, USA</i>		
End of Day 2				
18:00-21:30	IPFA 2019 BANQUET			

Time	5 July (Day 3)			
	Symposium Room II		Symposium Room I	
	Session 7A: Reliability and Failure Analysis of Power Devices Session Chair: Min Ren <i>UESTC, China</i>		Session 7B: Case Studies on Physical Failure Analysis Session Chair: Changze Liu <i>HiSilicon, China</i>	
08:30-09:00	Invited (7A.1)	Wear- and Short-Circuit Testing of Silicon Carbide Power MOSFETs Francesco Iannuzzo <i>Aalborg University, Denmark</i>	Invited (7B.1)	Failure and Materials Analysis in the Logic Integrated Circuit Industry: Status and Challenges in Advanced Nodes David Su <i>TSMC (Retired), Taiwan, R.O.C</i>
09:00-09:20	Paper ID: 132 (7A.2)	High Resolution Mapping of Defects at SiO₂/SiC Interfaces by Local-DLTS Based on Time-Resolved Scanning Nonlinear Dielectric Microscopy Yuji Yamagishi and Yasuo Cho <i>Tohoku University, Japan</i>	Paper ID: 219 (7B.2)	An Effective Monitored and Improved Method to Control Moisture for Outgoing FOSB Yi-Ying Chen, Chiu-E Tseng, Hsin-Wen Fan and Chih-Chao Pai <i>Powerchip Corporation, Taiwan, R.O.C</i>
09:20-09:40	Paper ID: 288 (7A.3)	Failure Analysis on TiAl Metallization Process for Ohmic Contact on 4H-SiC pMOSFET Chia Lung Hung, Jung-Chien Cheng and Bing-Yue Tsui <i>National Chiao Tung University, Taiwan, R.O.C</i>	Paper ID: 222 (7B.3)	The Application of Thermal Sensor to Locate IC Defects in Failure Analysis Authors: Kuan-Chieh Huang and Yi-Chen Lin, <i>Powerchip Corporation, Taiwan, R.O.C</i>
09:40-10:00	Paper ID: 228 (7A.4)	Repetitive-avalanche-induced Electrical Degradation and Optimization for 1.2kV 4H-SiC MOSFETs Hao Fu, Jiaying Wei, Siyang Liu, Wangran Wu and Weifeng Sun <i>Southeast University, China</i>	Paper ID: 165 (7B.4)	The Case of Failure Analysis of the PCBA Wire Corrosion under High Reliability Requirements Zheng Jie et al. <i>CEPREI, China</i>
10:00-10:20			Paper ID: 247 (7B.5)	Metallic Trace Contaminant Detection Using SEM/EDX Aaron Lee, Bernice Zee and Fang Jie Foo <i>AMD, Singapore</i>
10:20-10:40	Tea Break			

	Session 8A: Reliability and Failure Analysis of RF and Power Devices Session Chair: Liu Siyang, <i>Southeast University, China</i>		Session 8B: Advanced Physical Failure Analysis Techniques Session Chair: Wu Xing, <i>ECNU, China</i>	
10:40-11:10	Paper ID: 233 Invited (8A.1)	Reduction of current collapse in GaN (MIS)-HEMTs using dual material gate Binit Syamal and Xing Zhou <i>Nanyang Technological University, Singapore</i>	Invited (8B.1)	In-situ device microscopy Sun Litao <i>South East University, China</i>
11:10-11:30	Paper ID: 212 (8A.2)	100V Integrated Bootstrap Diode with Dynamic Field Limiting Rings for Solving Reverse Recovery Failure in GaN Gate Driver ICs Ajiang Li et al. <i>Southeast University, China</i>	Paper ID: 318 (8B.2)	Probing SRAM Signals for Yield Management Greg Johnson et al. <i>Carl Zeiss, USA</i>
^11:30-12:00 *11:30-11:50	^Invited (8A.3)	Hot Carrier reliability assessment strategies in advanced RF SOI technologies for 5G applications Dimitris P. Ioannou <i>Globalfoundries, USA</i>	*Paper ID: 146 (8B.3)	Simultaneous 2D carrier polarity (dC/dV) and density (dC/dz) distribution measurement of Si/SiC MOSFET based on scanning nonlinear dielectric microscopy Takehiro Yamaoka et al. <i>Hitachi High-Technologies Corporation, Japan</i>
11:50-13:00	Lunch			
	Session 9A: 2D Materials and Devices: Reliability and Failure Analysis Session Chair: Mario Lanza <i>Soochow University, China</i>		Session 9B: Emerging Technologies in Failure Analysis Techniques Session Chair: Zhigang Ji <i>Liverpool John Moores University, UK</i>	
13:00-13:30	Paper ID: 333 Invited (9A.1)	Reliability of 2D Field-Effect Transistors: from First Prototypes to Scalable Devices Yury Illarionov <i>TU Wien, Austria</i>	Invited (9B.1)	In situ TEM Study on Flexible Electronics Reliability and Failure Analysis Wu Xing <i>ECNU, China</i>
13:30-13:50	Paper ID: 181 (9A.2)	Performance Variability and Analog Behaviors of Memristive Devices with New Transition Metal Carbide Fei Gao et al. <i>Nanjing University of Posts and Telecommunications, China</i>	Paper ID: 290 (9B.2)	Study of Front-Side Approach to Retrieve Stored Data in Non Volatile Memory Devices Using Scanning Capacitance Microscopy Jing Yun Tay, Jason Cheah, Qing Liu and Chee Lip Gan <i>Nanyang Technological University, Singapore</i>

13:50-14:10	Paper ID: 324 (9A.3)	Low Power Resistance Switching Devices and Its High-Density Crossbar Arrays with a Novel 2D Material MXene for Performance Improvement of Reliability Nan He et al. <i>Nanjing University of Posts and Telecommunications, China</i>	Paper ID: 276 (9B.3)	The impact of endurance degradation in Analog RRAM for in-situ training Yuyi Liu, Bin Gao, Huaqiang Wu, Meiran Zhao and He Qian <i>Tsinghua University, China</i>
^14:10-14:40 *14:10-14:30	^Invited (9A.4)	Reliability Assessment for HfOx based Neuromorphic Devices / Systems Bin Gao <i>Tsinghua University, China</i>	*Paper ID: 265 (9B.4)	Generation and tracking of optical signals inside the IC to improve device security and failure analysis Elham Amini, Jean-Pierre Seifert and Christian Boit <i>TU Berlin, Germany</i>
14:30-15:00	Tea Break			
	Session 10A: Transistor and 2D Materials Reliability Session Chair: Nagarajan Raghavan <i>SUTD, Singapore</i>		Session 10B: Sample Preparation and Defect Characterisation Session Chair: Sun Litao <i>Southeast University, China</i>	
^15:00-15:30 *15:00-15:20	^Invited (10A.1)	Erroneous fabrication and reliability characterization of memristors: how to detect it? Mario Lanza <i>Soochow University, China</i>	*Paper ID: 249 (10B.1)	Application of Laser Deprocessing Technique in Physical Failure Analysis on Memory Bit-counting Yanlin Pan et al. <i>Globalfoundries, Singapore</i>
^15:30-16:00 *15:20-15:40	^Invited (10A.2)	Defect Properties and Charge Transport in h-BN / MoS2-based FET devices Kosuke Nagashio <i>University of Tokyo, Japan</i>	*Paper ID: 220 (10B.2)	Application of SIMS for the characterization of Nitrogen in TaN film Yun Wang et al. <i>Globalfoundries, Singapore</i>
15:40-16:00			Paper ID: 273 (10B.3)	Poly-Si Unetch Failure Due to Etching Rate Dependence of Si Orientation Dahyun Nam et al. <i>Samsung Electronics, Korea</i>
16:00-16:20	Paper ID: 299 (10A.3)	Tristate resistive switching analysis in graphene/hexagonal boron nitride/graphene cross-point memristors Kaichen Zhu et al. <i>Soochow University, China</i>	Paper ID: 277 (10B.4)	Three-dimensional Structure Recognition of Circuit Patterns on Semiconductor Devices Using Multiple SEM Images Detected in Different Electron Scattering Angles Kenji Yasui, Mayuka Osaki, Atsushi Miyamoto and Hitoshi Namai <i>Hitachi, Japan</i>

16:20-16:40	Paper ID: 284 (10A.4)	Light-Illumination-Induced Degradation and Its Long-Term Recovery in Indium-Tin-Zinc Oxide Thin-Film Transistors Meng Zhang et al. <i>Shenzhen University, China</i>	Paper ID: 214 (10B.5)	4-Point-Bending Characterization of Interfacial Adhesion Strength of Co-Zr-Ta and Co-Zr-Ta Variant Thin-Film Stacks Xintong Zhu et al. <i>Globalfoundries, Singapore</i>
16:40-17:10	Conference Closing Ceremony Best Poster Awards - Announcement Introduction to IPFA 2020, Marina Bay Sands, Singapore			
End of Day 3				